



**EXALTED PROCEDURE-RESPONSE AFTER FINAL REJECTION
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:	:	Conf. No.:
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Maria Ronay	:	
	:	
	:	
Serial No.: 09/577,347	:	Art Unit: 1765
	:	
Filed: May 24, 2000	:	Examiner: Perez Ramos, V.
	:	
For: Selective Polishing with	:	Atty Docket: YOR9-2000-0109
Slurries Containing	:	(20140/0247)
Polyelectrolytes	:	
	:	

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TC 1700

RESPONSE AFTER FINAL REJECTION UNDER 37 CFR § 1.116

Attention: Box AF
Commissioner for Patents
Washington, D.C. 20231

Siri:

This is in response to the Final Office Action dated July 23, 2002.

REMARKS

Claims 1 and 13-36 are now in the application. Claims 13-36 are directed to the elected invention. Claim 1 is directed to a non-elected invention and may be canceled by the Examiner by allowance of the claims directed to the elected invention.

Claims 13-21 were rejected under 35 U.S.C. § 103(a) as being unpatentable over U.S. Patent 5,645,736 to Allman. Allman does not render obvious the present invention.

The present invention provides for increasing the polishing ratio of silicon dioxide to silicon nitride by including an anionic polyelectrolyte in the polishing slurry. In addition, the present invention provides for increasing the ratio of a metal to silicon dioxide, silicon nitride, and/or silicon oxynitride by including a cationic polyelectrolyte in the polishing slurry. According to the present invention, as discussed in the paragraph